

Table I–11 to Subpart I of Part 98–Default Emission Factors (1–U_{ij}) for Gas Utilization Rates (U_{ij}) and By-Product Formation Rates (B_{ijk}) for Semiconductor Manufacturing for use with the Stack Test Method (150 mm and 200 mm wafers)														
All Processes	Process Gas i													
	CF ₄	C ₂ F ₆	CHF ₃	CH ₂ F ₂	C ₂ HF ₅	CH ₃ F	C ₃ F ₈	C ₄ F ₈	NF ₃	NF ₃ Remote	SF ₆	C ₄ F ₆	C ₅ F ₈	C ₄ F ₈ O
1-U _i	0.85	0.56	0.50	0.13	0.064	0.51	0.40	0.13	0.16	0.018	0.55	0.17	0.072	0.14
BCF ₄	NA	0.19	0.085	0.079	0.077	NA	0.20	0.11	0.045	0.015	0.13	0.13	NA	0.13
BC ₂ F ₆	0.046	NA	0.030	0.025	0.024	0.0034	NA	0.037	0.025	NA	0.11	0.11	0.014	0.045
BC ₄ F ₆	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA
BC ₄ F ₈	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA
BC ₃ F ₈	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA	NA
BC ₅ F ₈	0.0012	NA	0.0012	NA	NA	NA	NA	0.0086	NA	NA	NA	NA	NA	NA
BCHF ₃	0.10	0.047	NA	0.049	NA	NA	NA	0.040	NA	NA	0.0012	0.066	0.0039	NA

Notes: NA = Not applicable; i.e., there are no applicable emission factor measurements for this gas. This does not necessarily imply that a particular gas is not used in or emitted from a particular process sub-type or process type.